Advanced Vacuum PECVD #2 Operating Instructions

1) Login to your group/company directory.

2) Ensure you are on the Process & Start Job tabs on the bottom left side of the screen.

3) Start a coat (seasoning) recipe based on the material you want to deposit. Select recipe, Select Start Job.

4) When coat recipe is complete, Vent the chamber by selecting Vent on left side of screen.

5) Select Open Lid on the left side of the screen.

6) Using metal tweezers, load samples. To prevent whole wafers from moving, place 3-4 Si pieces around the wafer.

7) Select Close Lid on left side of screen.

8) Select Pump Down on left side of screen.

9) Select the deposition recipe. Select Start Job. Enter deposition time if prompted.

10) When process is complete, vent chamber by selecting Vent Chamber on left side of screen.

11) Select Open Lid on the left side of the screen.

12) Using metal tweezers, remove samples.

13) If total deposition time exceeded 29 minutes, wet clean only the upper chamber wall with DI water followed by Isopropyl. Do not touch/wipe the showerhead.

14) Select Close Lid on left side of screen.

15) Select Pump Chamber from the left side of menu.

16) Run a Cf4/O2 clean based on total (Coat + dep) length of deposition times.

17) Logout.

18) Record depositions and clean time in logbook.

Clean times:

DI water & Isopropyl upper+ chamber wall if total (Coat + dep) time exceeded 29 minutes.

SiO2 = 1 minute of clean for every 1 minute of deposition.

SiN = 1 minute of clean for every 7 minutes of deposition.